INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) TWI-6660	Application Number NEW	
Applicant(s)		
Jon Opsal et al.		
Filing Date	Group Art Unit	
HEREWITH	Unknown	

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	Ref	DOCUMENT NUMBER	DATE	Name	CLASS	SUBCLASS	FILING DATE
(Option	*A	4,468,136	08/28/1984	Murphy et al.	374	45	02/12/1982
M	*B	4,513,384	04/23/1985	Rosencwaig	364	563	06/18/1982
Or	*C	-4,521,118	06/04/1985	Rosencwaig	374	5	07/26/1982
110	*D	4,522,510	06/11/1985	Rosencwaig et al.	374	7	04/01/1983
av	*E	4,579,463	04/01/1986	Rosencwaig et al.	374	57	05/21/1984
(NV	*F	4,632,561	12/30/1986	Rosencwaig et al.	356	432	04/30/1985
The state of the s	*G	4,634,290	01/06/1987	Rosencwaig et al.	374	5	11/14/1985
	*H	4,636,088	01/13/1987	Rosencwaig et al.	374	5	05/21/1984
11/	*1	4,652,757	03/24/1987	Carver.	250	360.1	08/02/1985
	*]	4,710,030	12/01/1987	Tauc et al.	356	432	05/17/1985
	*K	4,750,822	06/14/1988	Rosencwaig et al.	356	445	03/28/1986
al -	*L	4,795,260	01/03/1989	Schuur et al.	356	400	05/15/1987
	*M	4,854,710	08/08/1989	Opsal et al.	356	432	07/23/1987
	*N	4,999,014	03/12/1991	Gold et al.	356	382	05/04/1989
W	+0	5,042,951	08/27/1991	Gold et al.	356	369	09/19/1989
	*P	5,074,669	12/24/1991	Opsal	356	445	12/12/1989
	*Q	5,159,412	10/27/1992	Willenborg et al.	356	445	03/15/1991
	*R	5,181,080	01/19/1993	Fanton et al.	356	381	12/23/1991
OD /	*S	5,228,776	07/20/1993	Smith et al.	374	5	05/06/1992
TIV .	•T	5,408,327	04/18/1995	Geiler et al.	356	432	07/14/1993
	•υ	5,657,754	08/19/1997	Rosencwaig	128	633	07/10/1995
	*V	5,978,074	. 11/02/1999	Opsal et al.	356	364	07/03/1997
	*W	6,191,846	02/20/2001	Opsal et al.	356	364	11/01/1999
W	*X	6.320,666	11/20/2001	Opsal et al.	356	601	10/16/2000

FOREIGN PATENT DOCUMENTS

Ĭ		DOCUMENT	ľ				TR	NSLATION
REF		NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	No
*Y _	Г	WO 83/03303	09/29/1983	PCT	G01N	21/63		
11	T	0.432 963 A2	06/19/1991	EPC	G01N	21/17		

OTHER DOCUMENTS
aclading Author, Title, Date, Pertinent Pages, Etc.)

	*AA	A. Rosencwaig, "Depth Promine of the atto Circuits with Thermal Wave Electron Microscopy," Electronic Letters,
•		20th Nov. 1980, Vol. 16, No. 24, pp. 32
	*AB	J. Opsal et al., "Thermal and plasma wave deput, of the circulture," Appl. Phys. Lett., 1 Sept. 1985, Vol. 47, No. 5,
		pp. 498-500.
	*AC	A. Rosencwaig, Chapters 17, 18, and 21 Photoacoustics and Photoacoustic Spectroscopy, 1980, pp. 207-244 (Chapts. 17-
		18) and 270-284 (Chapt. 21).
	*AD	X.D. Wu et al., "Photothermal microscope for high-T _c superconductors and charge density waves," Rev. Sci. Instrum.,
	1	Nov. 1993, Vol. 64, No. 11, pp. 3321-3327.
	*AE	J.T. Fanton et al., "High-sensitivity laser probe for photothermal measurements," Appl. Phys. Lett., 13 July 1987, Vol. 51,
ĺ]	No. 2, pp. 66-68.

Examiner	m val	Date Considered	August	2004		
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if						
not in conformance and not considered. Include conv of this form with next communication to applicant.						

Modified Form PTO-A820 (also form PTO-1449)

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)

Docket Number (Optional)	Application Number		
TWI-6640	NEW		
Applicant(s)			
Jon Opsal et al.			
Filing Date	Group Art Unit		
HEREWITH	Unknown		

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	Ref	DOCUMENT NUMBER	DATE	Name	CLASS	SUBCLASS	FILING DA	\TE
-	<u> </u>		F	OREIGN PATENT DOC	CUMENTS			
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

1	*AF	J.T. Fanton et a "Dev-Temperature Photothermal Measurements of High T _c Superconductors," The Review of Progress in Quantitative Nonactructive Naturation (Reprint G.L. Report No. 4728 [Aug. 1990]), Presented July 15-20, 1990, 8 pages
		in length.
	*AG	B.C. Forget et al., "Electronical "As yith measurement in silicon by photothermal microscopy," Appl. Phys. Lett., 19 Aug. 1996, Vol. 69, No. 8, pp. 1107
	*AH	J.T. Fanton et al., "Multiparameter recusurements of thin films using beam-profile reflectometry," Journal of Applied Physics, 1 June 1993, Vol. 73, No. 11, pp. 7035 2000.
	*Al	G. Langer et al., "Thermal conductivity of thin stablic films measured by photothermal profile analysis," Rev. Sci. Instrum., Vol. 68 (3), March 1997, pp. 1510-1513
	*AJ	G. Savignat et al., "Non-destructive characterization from a ories by mirage effect and photothermal microscopy," Journal De Physique IV, Colloque C7, supplement au Jo. gnal de Physique III, Vol. 3, Nov. 1993, pp. 1267-1272.
	*AK	M.B. Suddendorf et al., "Noncontacting measurement of opaque fill films using a dual beam thermal wave probe," Appl. Phys. Lett., Vol. 62 (25), 21 June 1993, pp. 3256-3258.
	*AL	M. Liu et al., "Response of interferometer based probe systems to pin toda pleatent in layered media," J. Appl. Phys., Vol. 76 (1), 1 July 1994, pp. 207-215.
	*AM	J.F. Bisson et al., "Influence of diffraction on low thermal diffusivity measurements with infrared photothermal microscopy," J. Appl. Phys., Vol. 83 (2), 15 January 1998, pp. 1036-1042.
	*AN	E.P. Visser et al., "Measurement of thermal diffusion in thin films using a modulated lase (es. sigue: Application to chemical-vapor-deposited diamond films," J. Appl. Phys., Vol. 71 (7), 1 April 1992, pp. 3238-248.
	*A0	L. Pottier, "Micrometer scale visualization of thermal waves by photoreflectance microscopy, April Phys. Lett., Vol. 64 (13), 28 March 1994, pp. 1618-1619.
	*AP	A.M. Mansanares et al., "Photothermal microscopy: Thermal contrast at grain interface in sintered metallic interials," J. Appl. Phys., Vol. 75 (7), 1 April 1994, pp. 3344-3350.
-	*AQ	A.M. Mansanares et al., "Temperature field determination of InGaAsP/InP lasers by photothermal microscopy. Evide ce for weak nonradiative processes at the facets," Appl. Phys. Lett., Vol. 64 (1), 3 January 1994, pp. 4-6.
	*AR	Jian-Chun Cheng et al., "Theoretical studies of pulsed photothermal phenomena in semiconductors," J. Appl. Phys., Vol. 74, No. 9, 1 November 1993, pp. 5718-5725.

Examiner Company Compa	Date Considered 19 Augus 7 2004					
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if						
not in conformance and not considered. Include copy of this form with next communication to applicant.						